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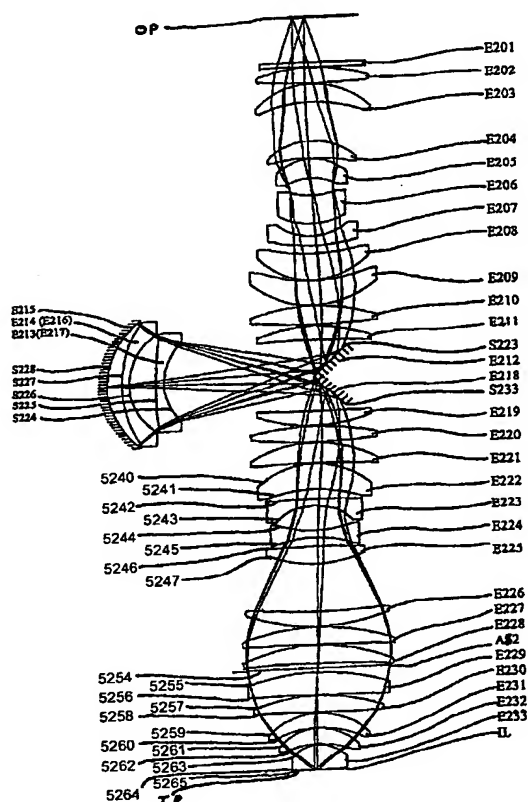
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(54) Title: PROJECTION OPTICAL SYSTEM AND METHOD FOR PHOTOLITHOGRAPHY AND EXPOSURE APPARATUS AND METHOD USING SAME



(57) Abstract: Optical Projection System and Method for Photolithography. A lithographic immersion projection system and method for projecting an image at high resolution over a wide field of view. The projection system and method include a final lens which decreases the marginal ray angle of the optical path before light passes into the immersion liquid to impinge on the image plane.

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